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Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No. NOVLP068/NVLS-2818	Application No.: 10/690,084
	Applicant: Koos et al. Filing Date October 20, 2003	Group 1765

U.S. Patent and Publication Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
/LV/	A1	7,008,871	03/2006	Andricacos et al.			
	A2	5,913,147	06/1999	Dubin et al.			
	A3	6,136,707	10/2000	Cohen			
	A4	5,891,513	04/1999	Dubin et al.			
	A5	6,065,424	05/2000	Shacham-Diamond et al.			
	A6	5,969,422	10/1999	Ting et al.			
	A7	5,972,192	10/1999	Dubin et al.			
	A8	5,576,052	11/1996	Arledge et al.			
	A9	5,151,168	09/1992	Gilton et al.			
	A10	5,674,787	10/1997	Zhao et al.			
	A11	6,197,181	03/2001	Chen			
	A12	4,981,725	01/1991	Nuzzi et al.			
	A13	5,318,803	06/1994	Bickford et al.			
	A14	6,398,855	06/2002	Palmans et al.			
	A15	5,382,447	01/1995	Kaja et al.			
	A16	2003/0059538	03/2003	Chung et al.			
	A17	6,174,353	01/2001	Yuan et al.			
	A18	2004/0065540	04/2004	Chebiam et al. 11/2003			
	A19	6,645,567	11/2003	Mayer et al.			
	A20	2003/0075808	04/2003	Inoue et al.			
✓	A21	4,737,446	04/1988	Cohen et al.			
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Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
/LV/	B1	99/47731	09/23/99	WIPO			X	
Examiner /Lan Vinh/				Date Considered 03/21/2007				

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



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U.S. Patent and Publication Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
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	A2	6,692,873	11/8/05	Park 2/2004			
	A3	5,824,599	10/20/98	Schacham-Diamond, et al.			
	A4	5,695,810	12/9/97	Dubin et al.			
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	A7	2002/0084529	07/2002	Dubin et al.			
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Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
LV	B1	JP03122266	05/1991	JPO				

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
LV	C1	Sullivan et al, "Electrolessly Deposited Diffusion Barriers For Microelectronics, E. J. IBM J Res Develop Vol 42, No. 4 Sept 1998, 607-620
LV	C2	Eugene J. O'Sullivan, "Electroless Deposition in Microelectronics: New Trend," Electrochemical Society Proceeding Volume 99-34, 159-171
LV	C3	T. Itabashi et al., "Electroless Deposited CoWB for Copper Diffusion Barrier Metals," Hitachi Research Laboratory, IEEE, 2002, 285-287
LV	C4	N. Petrov and Y. Shacham-Diamond, "Electrochemical Study of the Electroless Deposition of Co(W,P) Barrier Layers for Cu Metallization," Electrochemical Soc. Proceedings Vol. 2000-27, 134-148
Examiner /Lan Vinh/		Date Considered 11/22/2006

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U.S. Patent and Publication Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
LV	A1	2005/0158985	06.21.05	Chen et al.			
LV	A2	6,884,724 B2	04.26.05	Hsu et al.			

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Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	B1							

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	C1	
Examiner LAN VINH		Date Considered 2/8/06

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